

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

Information Disclosure Citation in an Application	Application No.	Applicant(s)	
	10/635,962	Larry E. Hieb	
	Docket Number 065618.0109	Group Art Unit 3653	Filing Date August 7, 2003

U.S. PATENT DOCUMENTS

	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
MPE A	3,556,345	01/19/71	Rowekamp	221	242	05/27/68
MPE B	3,674,175	07/04/72	Jaquish	221	92	11/12/70
MPE C	3,684,131	08/15/72	Kurimsky	221	242	04/22/70
MPE D	3,757,998	09/11/73	Millies et al.	221	242	12/08/71
MPE E	3,883,038	05/13/75	Bookout	221	67	11/12/73
MPE F	4,096,969	06/27/78	Ragusa	221	199	05/09/77
MPE G	4,168,784	09/25/79	Heler	221	125	10/05/77
MPE H	4,254,892	03/10/81	Lee	221	90	08/06/79
MPE I	4,757,915	07/19/88	Albright et al.	221	75	08/25/86
MPE J	4,846,367	07/11/89	Gulgan et al.	221	81	07/01/87
MPE K	4,940,161	07/10/90	Hieb	221	67	06/28/88
MPE L	4,986,615	01/22/91	Hieb et al.	312	45	10/17/88
MPE M	5,127,546	07/07/92	Chen	221	242	08/08/91
MPE N	5,511,646	04/30/96	Maldanis et al.	194	217	06/03/93
MPE O	5,516,003	05/14/96	Hebert	221	130	11/28/94
MPE P	5,529,207	06/25/96	Oden et al.	221	67	01/25/95
MPE Q	5,799,823	09/01/98	Feltrin	221	298	10/28/96
MPE R	US 6,179,161 B1	01/30/01	Kovens et al.	221	131	11/13/98
MPE S	US 6,302,293 B1	10/16/01	Wittern, Jr., et al.	221	92	04/16/99
MPE T	US 6,513,887, B2	02/04/03	Paczkowski et al.	312	45	01/05/01

FOREIGN PATENT DOCUMENTS

	DOCUMENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION
						YES
MPE U	PCT/US03/024897	08/07/03	PCT			

NON-PATENT DOCUMENTS

	DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE

EXAMINER	DATE CONSIDERED
Michael E. Bruck	12/9/05

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